

LISTING OF CLAIMS

Claims 1-25 (Canceled).

26. (Previously Presented) A plasma etching composition comprising:

at least two fluorocarbons and ammonia, wherein said at least two fluorocarbons and said ammonia form a reactive mixture, and

wherein said at least two fluorocarbons are selected from the group consisting of fluorohydrocarbons, chlorofluorocarbons, and chlorofluorohydrocarbons.

Claims 27-76 (Canceled).

77. (Previously Presented) A plasma etching composition comprising:

at least one fluorocarbon, oxygen, and ammonia, wherein said at least one fluorocarbon, said oxygen, and said ammonia form a reactive mixture.

78. (Previously Presented) A plasma etching composition comprising:

at least two fluorocarbons and ammonia, wherein said at least two fluorocarbons and said ammonia form a reactive mixture, and

wherein at least one of said at least two fluorocarbons are selected from the group consisting of C_4F_8 , C_4F_6 , C_5F_8 , C_3F_8 , and CH_2F_2 .

79. (Previously Presented) The composition of claim 78, wherein at least one of said at least two fluorocarbons is CH_2F_2 .

80. (Previously Presented) The composition of claim 79, wherein said at least two fluorocarbons are CF_4 , CHF_3 , and CH_2F_2 .

81. (Previously Presented) The composition of claim 78, further comprising:

at least one of oxygen and nitrogen.

82. (Previously Presented) The composition of claim 26, further comprising:

at least one of oxygen and nitrogen.